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ABSTRACT OF THE DISCLOSURE

0030 A semiconductor design patternable on a semiconductor wafer for improved detection of out-of-focus conditions during lithographic processing is disclosed. The semiconductor design includes a central main body, and at least one arm extending from sides of the central main body. Each arm has a first one or more at least substantially triangular shapes, and a disconnected second one or more at least substantially triangular shapes. A tip of the first shapes is positioned opposite a tip of the second shapes, such that a gap there between is formed. The gap is sensitive to out-of-focus conditions during lithographic processing, where the gap increases as defocus increases. Increasing of the gap as defocus increases is preferably automatically detectable by semiconductor test equipment.